Surface chemistry during atomic layer deposition of Pt studied with vibrational sum-frequency generation

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Figure: The key features of the reaction mechanism of Pt ALD using MeCpPtMe₃ and O₂ (g) as precursor and co-reactant, respectively. At the beginning of the Pt half-cycle, there is a significant amount of atomic O adsorbed on the Pt surface. (a1) The MeCpPtMe₃ precursor adsorbs on this surface. (a2) Some of the ligands are combusted to CO₂ (g) and H₂O(g) by the adsorbed atomic O. Other ligands either remain intact or dehydrogenate to form adsorbed C_xH_y (ads) and H(ads). (a3) Some of the ligands recombine with adsorbed H on the surface to form CH₄ (g). In the co-reactant half-cycle, molecular O₂ (g) dissociates on the catalytic Pt surface and reacts with the remaining hydrocarbons groups forming CO₂ (g) and H₂O(g). Furthermore, the surface is saturated with atomic O adsorbed on the surface.



Figure: (left) BB-SFG spectra of the Pt surface as a function of precursor exposure for ALD at 250C, each spectrum has been offset for clarity. The increase in the broad spectral shape is related to coverage of the C=C groups. The dip at 2950 cm⁻¹ is the signature of the CH₃ groups on the surface. (right) The normalized coverage of the C=C groups and the CH₃ groups obtained from a fit to the BB-SFG spectra (dashed lines in the left figure). The saturation of the C=C precedes the saturation of the CH₃ contributions.